

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1 (Cancelled):

2 (Currently Amended): An exposure apparatus according to claim 1, comprising:
a projection optical system for projecting a pattern of a mask onto a substrate; and
a fluid supply unit for supplying a fluid between said projection optical system
and the substrate, said fluid supply unit including an injection unit for injecting carbon dioxide
into the fluid,

wherein said fluid supply unit includes a degassing unit for degassing the fluid,
said degassing unit being located at an upstream side of the injection unit.

3(Currently Amended): An exposure apparatus according to claim [[1]] 2, wherein said
injection apparatus includes a membrane module for injecting the carbon dioxide.

4 (Currently Amended): An exposure apparatus according to claim [[1]] 2, wherein the
injection unit injects the carbon dioxide at a concentration of the carbon dioxide in the fluid
between 0.02 ppm and 750 ppm.

5 (Original): An exposure apparatus according to claim 4, wherein the injection unit injects the
carbon dioxide at the concentration of the carbon dioxide in the fluid between 0.06 ppm and 300
ppm.

6 (Currently Amended): An exposure apparatus according to claim [[1]] 2, wherein the fluid supply unit includes a resistivity meter for measuring a resistivity value of the fluid, and the injection unit injects the carbon dioxide based on a measurement result of the resistivity meter.

7 (Currently Amended): An exposure apparatus according to claim [[1]] 2, wherein the injection unit injects the carbon dioxide so that a resistivity value of the fluid is between 0.02 MΩ·cm and 10 MΩ·cm.

8 (Original): An exposure apparatus according to claim 7, wherein the injection unit injects the carbon dioxide so that the resistivity value of the fluid is between 0.04 MΩ·cm and 5 MΩ·cm.

9-12 (Cancelled):

13(Currently Amended): A device manufacturing method comprising the steps of:
exposing an object using an exposure apparatus according to claim [[1]] 2 and
developing the exposed object.

14-23 (Canceled):